



China Compound Semiconductor Standards Committee

Meeting Agenda

China Fall Standards Meeting
Wednesday, September 22nd, 2021, 13:30 --16:45
Wuhu, Anhui, China

| Time | Topic | Presenter |
|-------------|--|---|
| 13:00 | Registration | |
| 13:30 | Welcome / Call to Order <ul style="list-style-type: none">• Opening Remark• Introductions• Meeting Reminders• Agenda Review | Co-chair All SEMI Staff Co-chair |
| 13:50 | Review and Approval of Previous Meeting Minutes | SEMI Staff |
| 13:55 | SEMI Staff Report | SEMI Staff |
| 14:00 | Liaison Reports <ul style="list-style-type: none">• North America CSM Committee• Europe CSM Committee• Japan CSM Committee | SEMI Staff SEMI Staff SEMI Staff |
| 14:15 | TF Reports <ul style="list-style-type: none">• SiC Epitaxial Wafer Task Force• Silicon Carbide Substrate Task Force | Gan FENG – Epiworld Min LU – MigeLab |
| 15:00 | Documents Request for Ballots <ul style="list-style-type: none">• Doc. 6693, New Standard: Specification for 4H-SiC Homo-Epitaxial Wafer• Doc. 6767, Test Method for Flatness of Silicon Carbide Wafers by Optical Interference• Doc. 6768, Test Method for Micropipe Density of Silicon Carbide Wafer by Laser Reflection• Doc. 6769, Test Method for Residual Stress of Silicon Carbide Wafers by Photoelastic | Gan FENG – Epiworld Min LU – MigeLab Min LU – MigeLab Min LU – MigeLab |
| 16:00 | New Action Items | SEMI Staff |
| 16:05 | Next Meeting Date & Locale <ul style="list-style-type: none">• Next Meeting Time of the China Compound Semiconductor Materials Standards Committee | |
| 16:10 | Group Photo | |
| 16:20 | Core Members Application and Renew | |
| 16:45 | Adjournment | |